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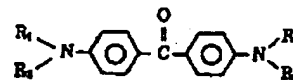
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(54) PHOTOPOLYMERIZABLE COMPOSITION

(57)Abstract:

PURPOSE: To obtain a photopolymerizable composition having superior sensitivity and suitable for use as a photoresist for fine working by mixing a specified addition-polymerizable compound with oxime ester and aminophenyl ketone.

CONSTITUTION: One or more kinds of addition-polymerizable compounds (A) each having 100°C b.p. under ordinary pressure such as diethylene glycol dimethacrylate and divinyl phthalate are mixed with oxime ester (B) having 40W 63kcal/mol triplet energy such as 2-acetylnaphthalene-o-acetyloxime and aminophenyl ketone (C) represented by the formula (where each of R₁WR₄ is H or 1W 4C alkyl) to obtain the desired photopolymerizable composition. A preferred example of the aminophenyl ketone represented by the formula is 4,4'-bis(dimethylamino)benzophenone.



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